

# Some basics of the PITZ vacuum system

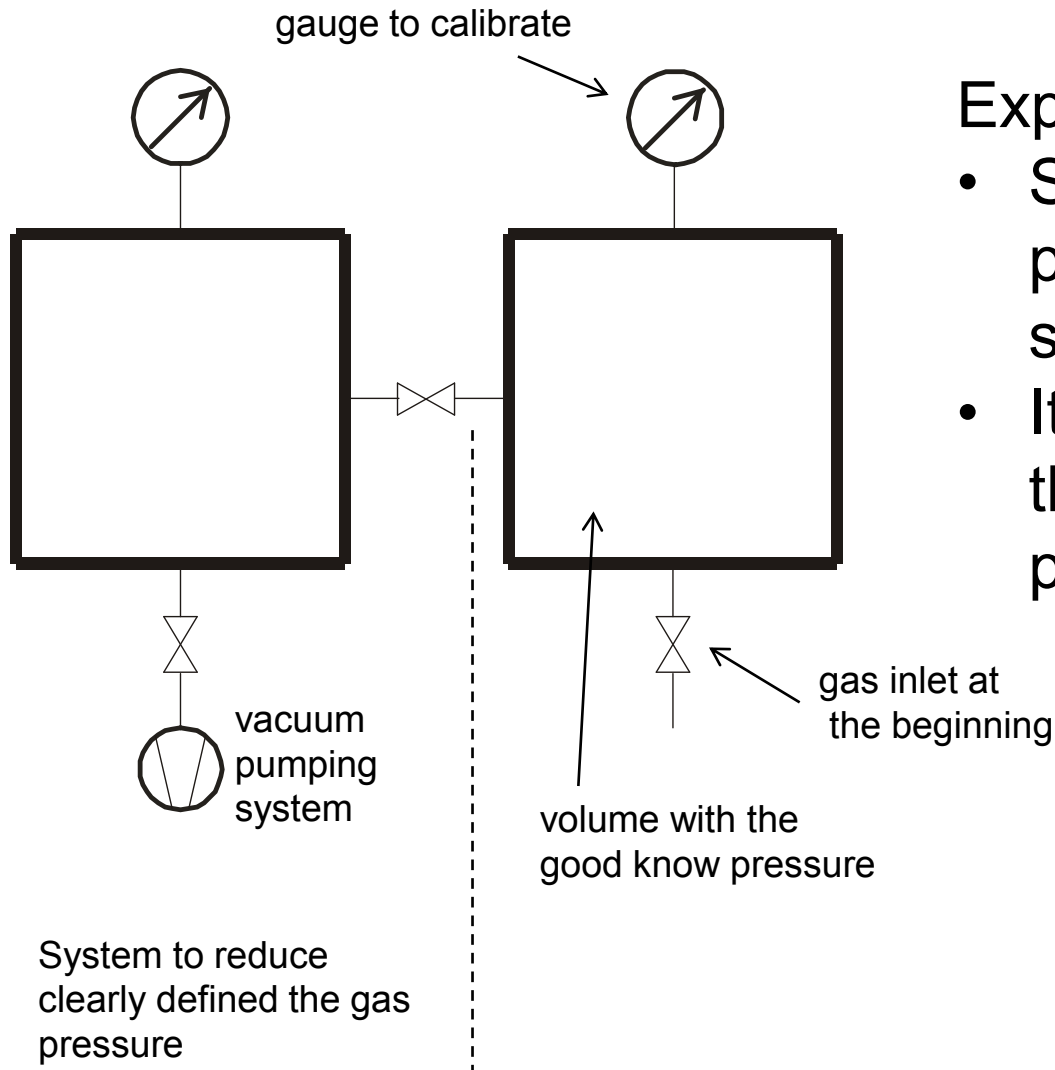
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und Energie

(BESSY II)

- We try to understand what is that – UHV
- Generation of vacuum at PITZ
- Methods to measure the total pressure
- A method to get partial pressures (RGA)
- Gas currents in an accelerator setup
- One of the influences of the plasma chamber on the PITZ vacuum system

# Ultra high vacuum – what's that?

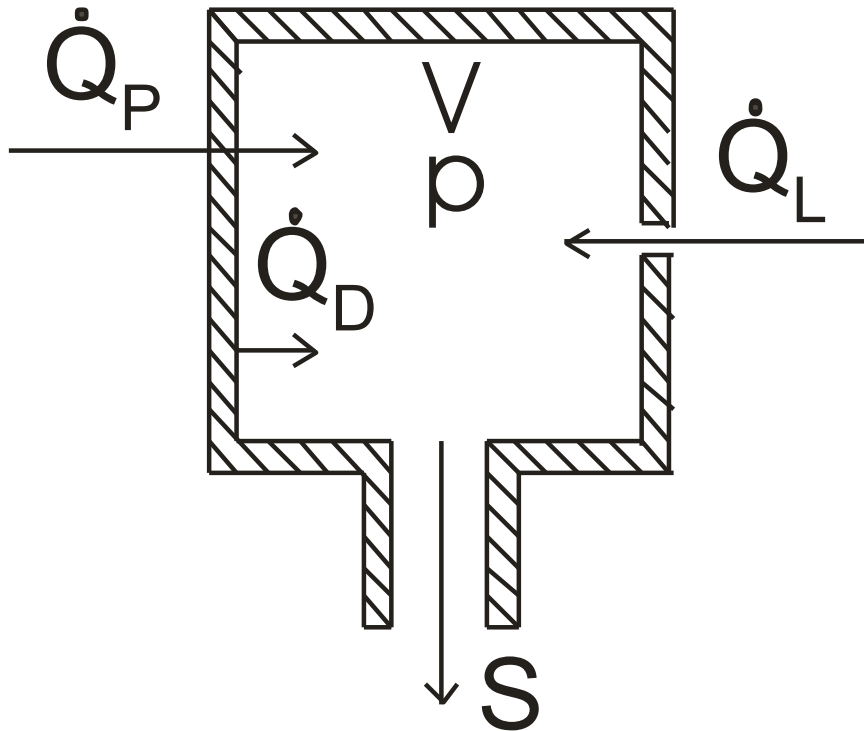


## Experiment:

- Setup to calibrate a pressure measurement system
- It will not work properly in the ultra high vacuum pressure range

- Let's assume that we have at some places a total pressure of  $10^{-8}$  Pa =  $10^{-10}$  mbar
- 13 orders of magnitude smaller than normal pressure
- $10^{13}$  s = 317098 years (Homo Sapiens exists about 130000 years )
- Particle density = 2 700 000 cm<sup>-3</sup>
- Average free path length = 590 km (Berlin – Munich)
- impingement rate =  $3 \times 10^{10}$  cm<sup>-2</sup> s<sup>-1</sup>
- collision rate =  $7,7 \times 10^{-4}$  s<sup>-1</sup>,  
i. e. time between a collision of two particles is 44 min

# Gas balance of an UHV-chamber



$\dot{Q}_L$  ... *Leak gas current*

$\dot{Q}_P$  ... *Permeation gas current*

$\dot{Q}_D$  ... *Desorption gas current*

$p$  ... *pressure*

$V$  ... *volume*

$S$  ... *pumping speed (no gas current)*

$$\dot{Q} = \frac{\text{amount of gas}}{\text{time}} = \frac{d}{dt} (p \cdot V) = V \frac{dp}{dt}$$

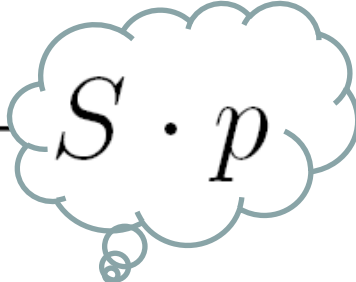
$$\dot{Q}_{\text{rate}} = \frac{\text{gas current}}{\text{area}} = \frac{\dot{Q}}{A} = \frac{V}{A} \frac{dp}{dt}$$

# Realistic assumptions:

no leaks

no permeation gas current

$$\dot{Q}_L = 0, \quad \dot{Q}_P = 0 \quad \text{and} \quad \dot{Q}_D = \dot{Q}$$

$$\frac{d}{dt}(V \cdot p) = V \frac{dp}{dt} = \dot{Q} - S \cdot p$$


gas current due  
to the pump

# Pumping down:

$$p(t = 0) = p_0$$

$$p(t) = \left( p_0 - \frac{\dot{Q}}{S} \right) e^{-\frac{S}{V} \cdot t} + \frac{\dot{Q}}{S}$$

$$\frac{\dot{Q}}{S} = p_{stat} \quad \text{basic pressure}$$



# At the beginning

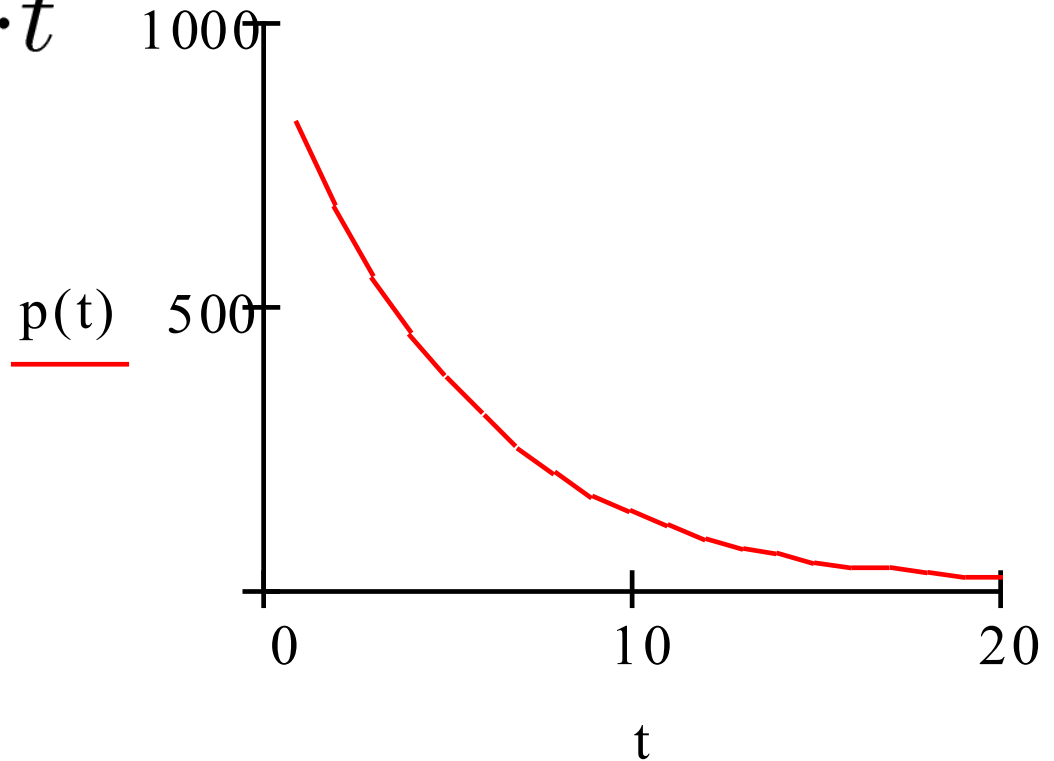
the desorption gas current is negligible

$$p(t) = p_0 e^{-\frac{S}{V} \cdot t}$$

$$p_0 = 1000 \text{ mbar}$$

$$V = 10 \text{ l}$$

$$S = 2 \frac{\text{l}}{\text{s}}$$



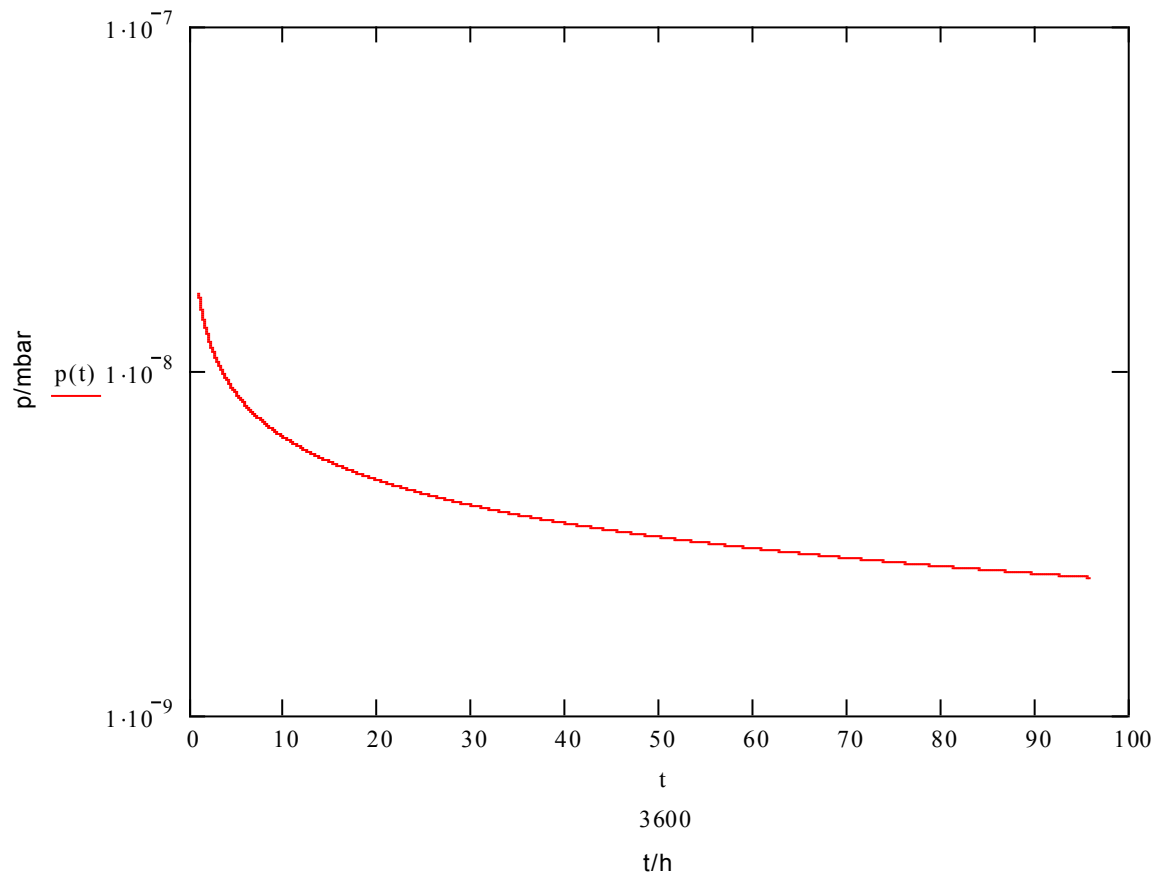
# But then...

In the UHV-range the desorption gas current is not constant

If we have a metallic chamber the gas load is decreasing approximately with

$$\dot{Q}(t) = \dot{Q}_0 \cdot t^{-m} \quad \text{with} \quad m \approx \frac{1}{2}$$

empirical  
assumption for  
metals



$V = 1 \text{ l}, S = 0,82 \text{ l/s}$   
baked chamber  
after cooling down

## Pressure increasing in the UHV range

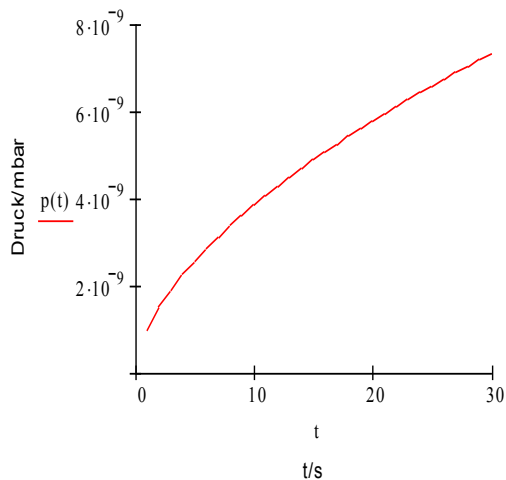
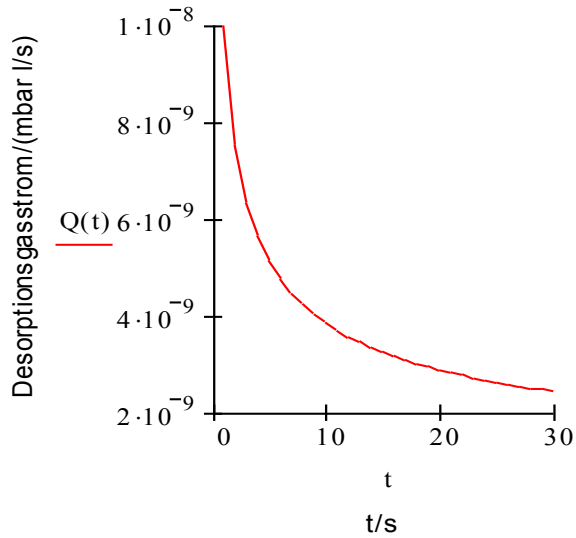
using  $\frac{d}{dt}(V \cdot p) = V \frac{dp}{dt} = \dot{Q} - S \cdot p$

We get with  $p(0) = 0$   $p(t) = \frac{\dot{Q}}{S} \left( 1 - e^{-\frac{S}{V} \cdot t} \right)$

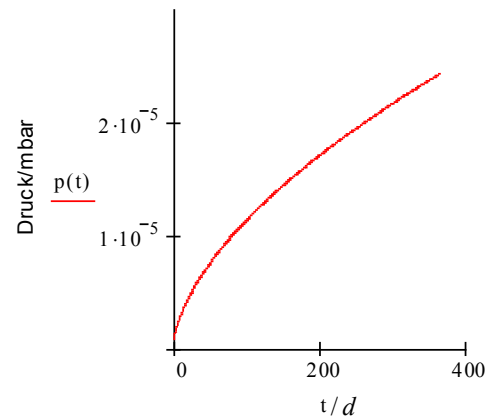
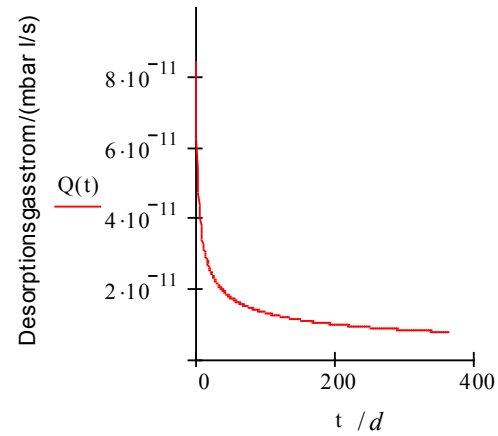
$$p(t) = \lim_{S \rightarrow 0} \left( \frac{\dot{Q}(t)}{S} \left( 1 - e^{-\frac{S}{V} \cdot t} \right) \right) = \dot{Q}(t) \cdot \frac{t}{V}$$

# Realistic pressure increasing

after some seconds...



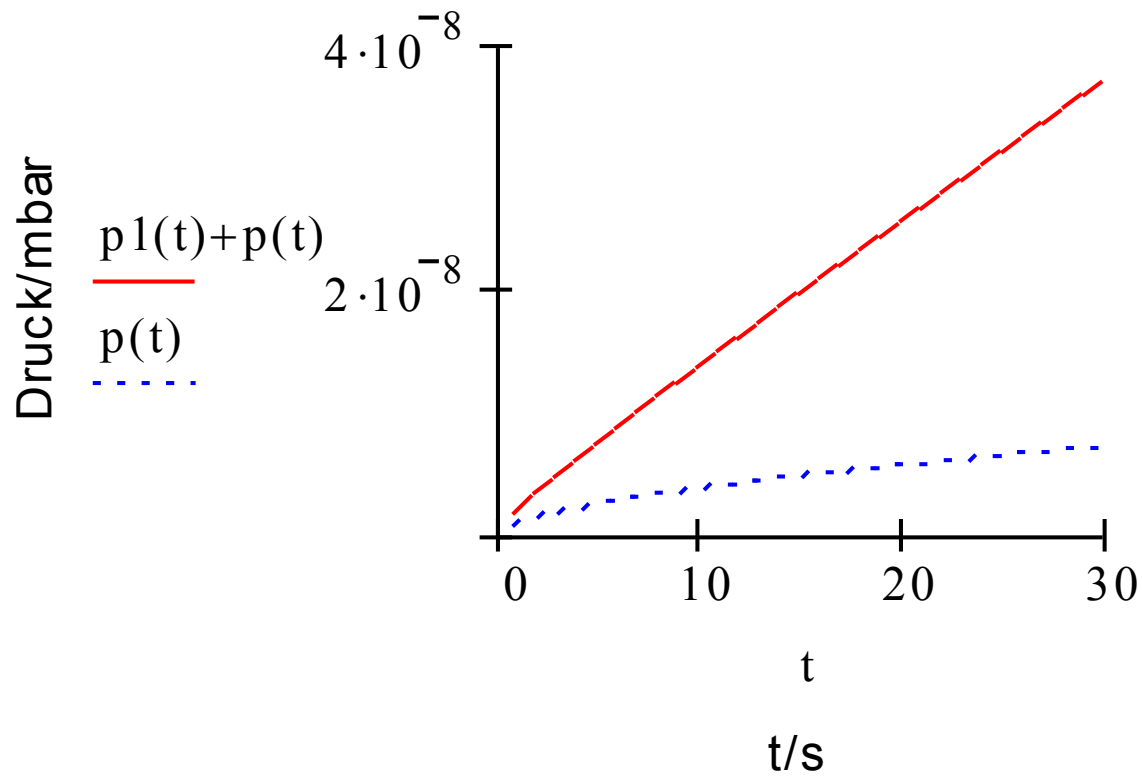
and after one year



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# What is a leak at a flange connection?

- A metallic flange connection should have a leak rate less than  $1 \times 10^{-11}$  mbar l s<sup>-1</sup>.
- That means, 1 cm<sup>3</sup> of a gas needs more than 3171 years to flow into the vacuum chamber passing the flange connection.



desorption + leak

desorption

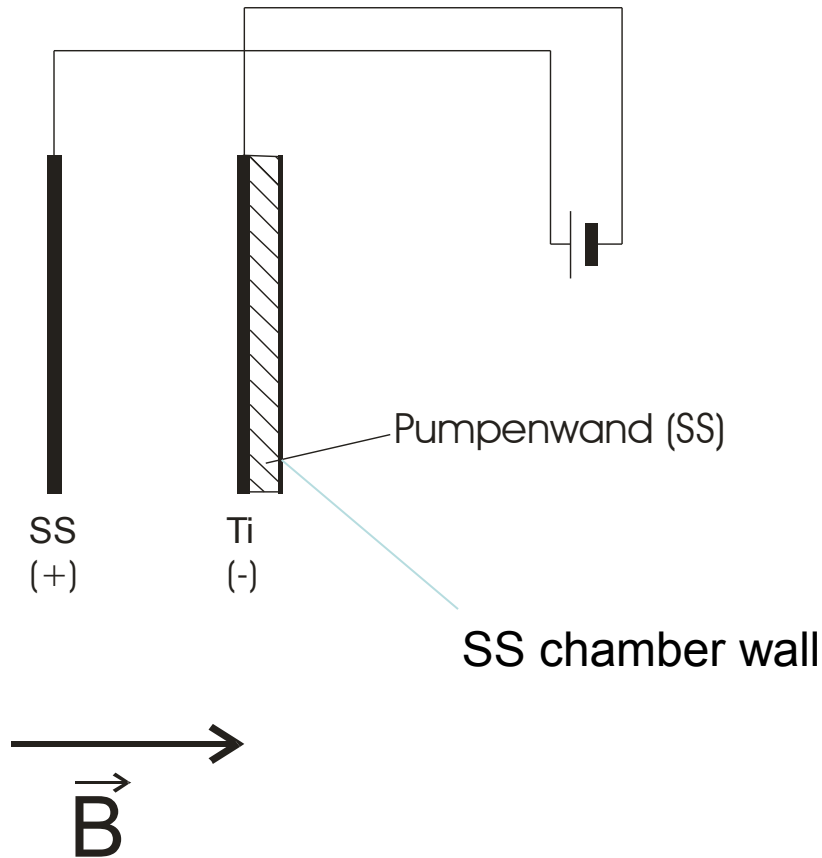
# Generation of vacuum

- Using a fore-vacuum pump in connection with a turbo molecular pump to get a pressure in the high vacuum range.
- Baking of the most important vacuum components to reduce the desorption gas flow.
- Using of ion getter pumps and sometimes of titanium sublimation pumps to get a pressure in the ultra high vacuum range.



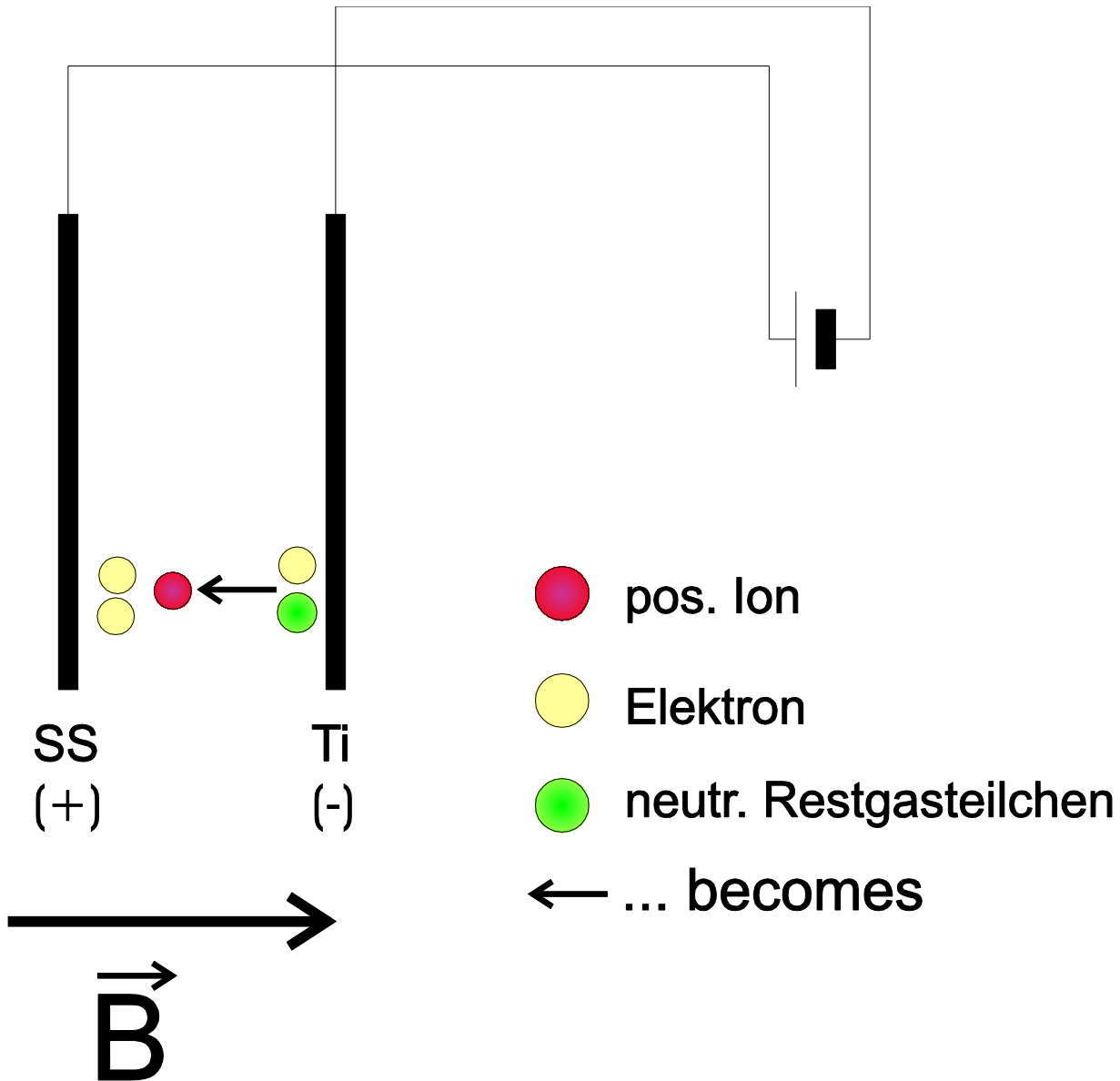
# Ion getter pump

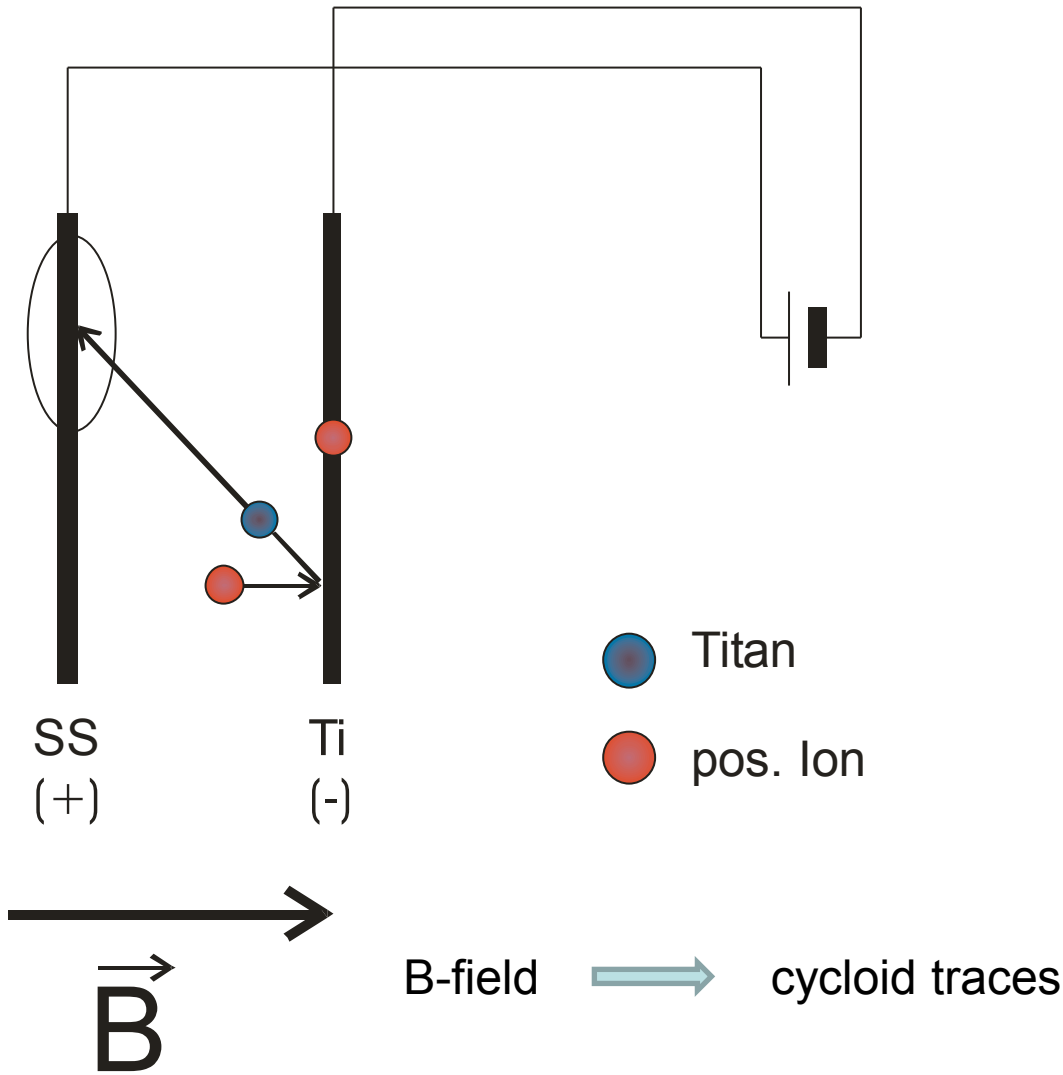
diode



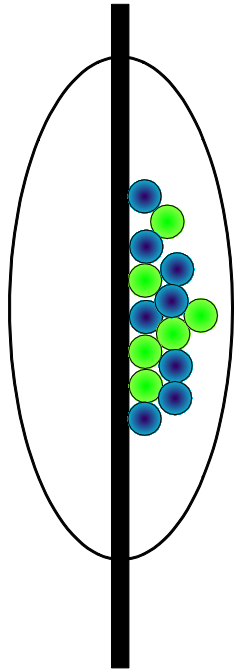
Ti ...ground

Positive high voltage  
from a power supply,  
(3...6) kV





- ion implantation into the cathode surface (pump effect, memory effect)
- Sputtering of the Ti plate
- Ti atoms beat the SS surface



- titanium
- neutral residual gas particle

3 possibilities at the anode ( $\approx 95\%$ )

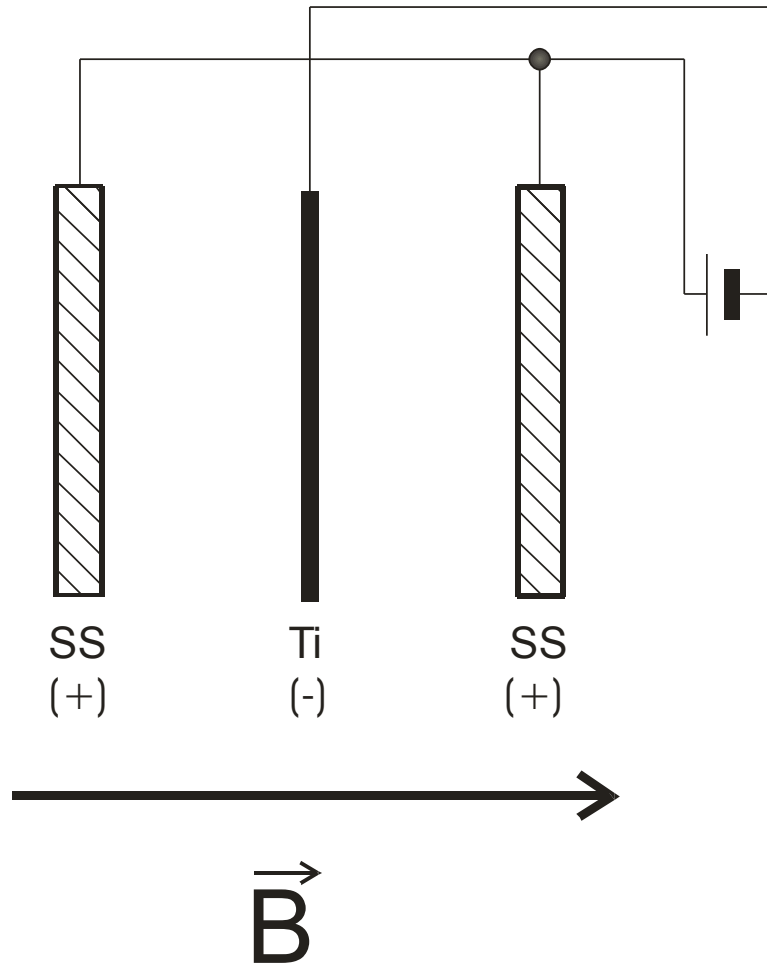
- covering atoms
- physical compound
- chemical compound

no noble gases

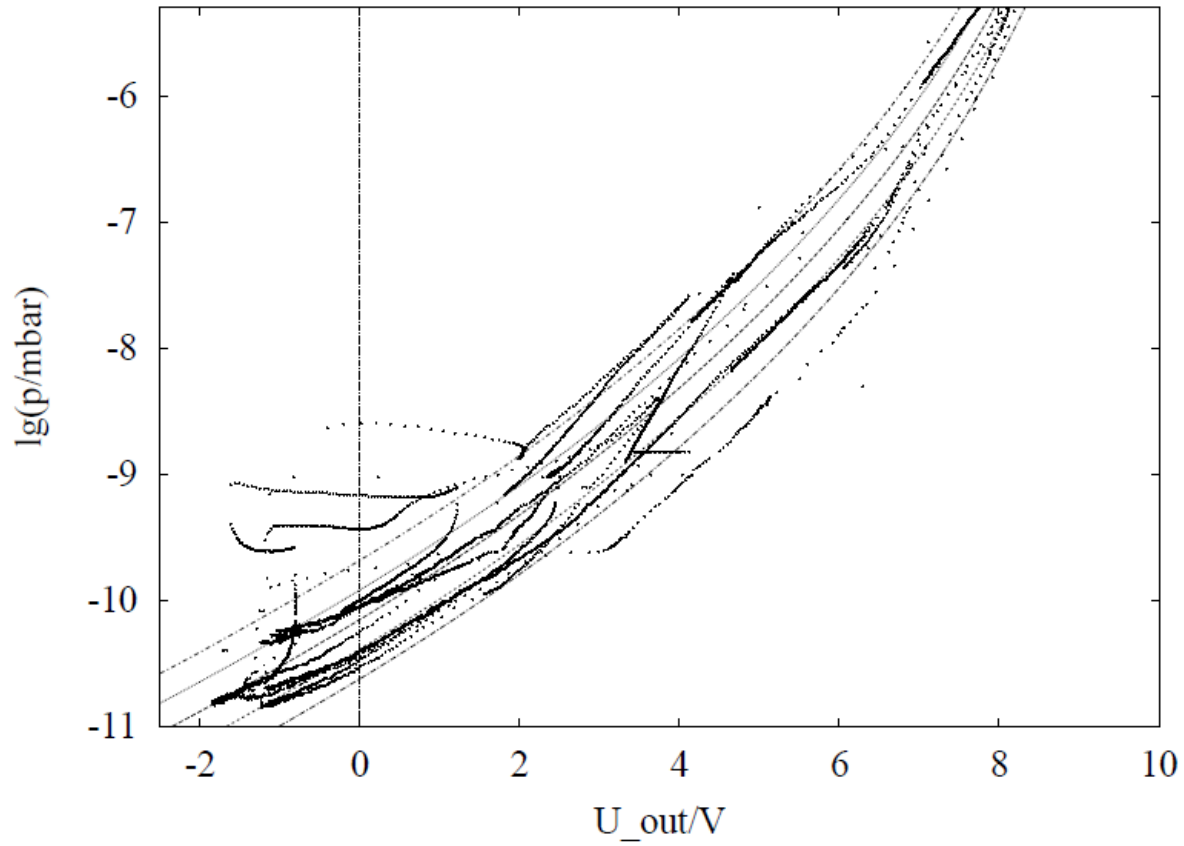
The only possibility to pump noble gases consists in ion implantation into the cathode surface ( $\approx 5\%$ )

Pumping speed increases, if the pressure, i. e. the gas load, increases

# Triode

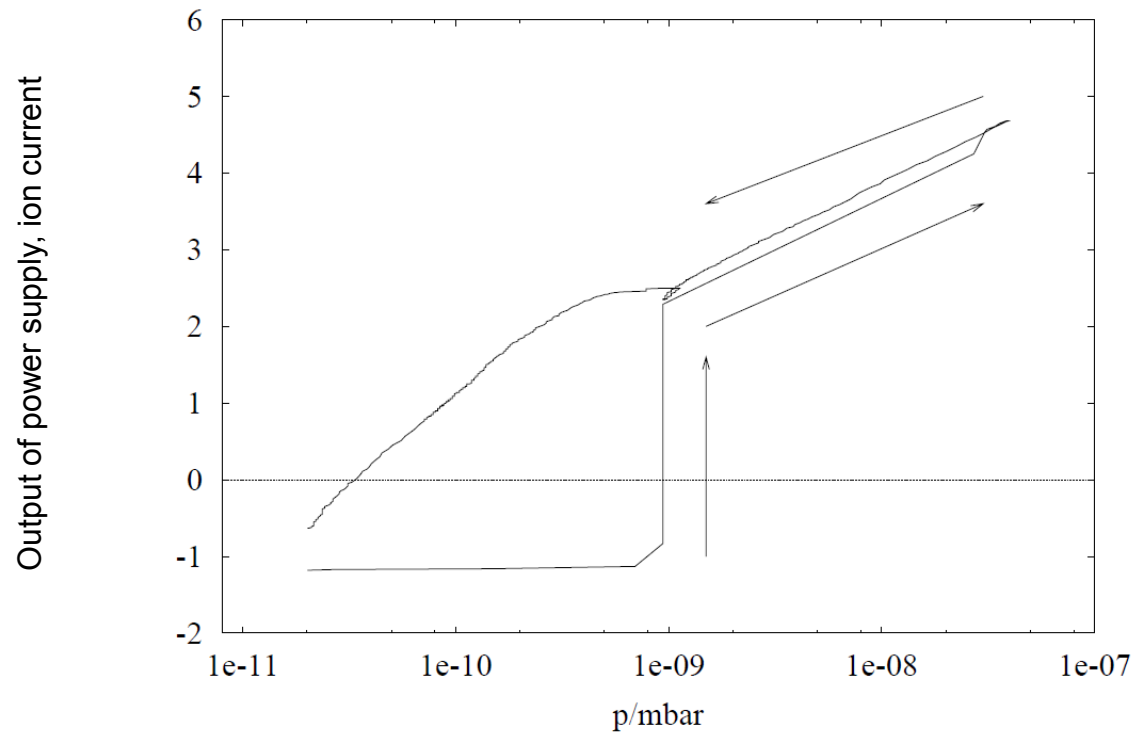


Ti ... negative high  
Voltage, (-6...-3) kV

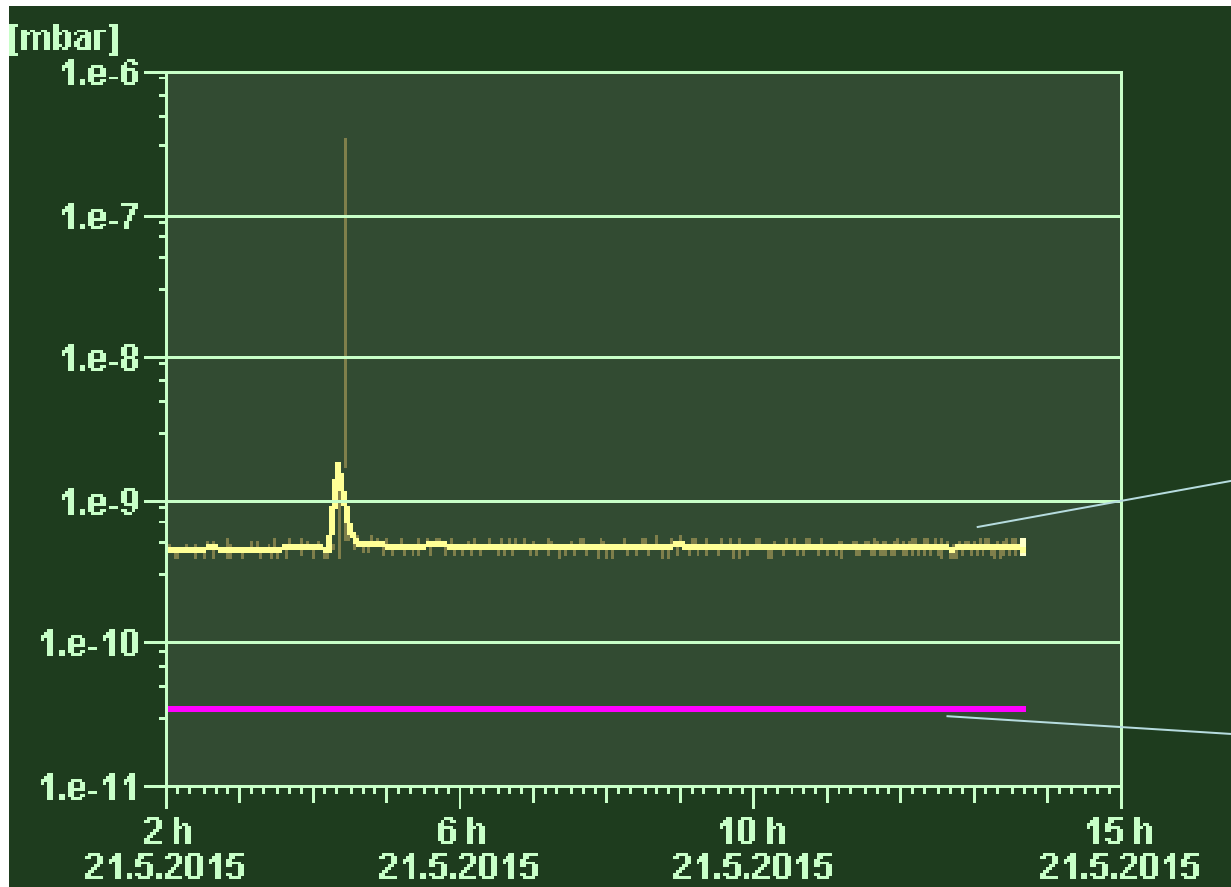


Calibration of the ion getter pump to get the pressure values

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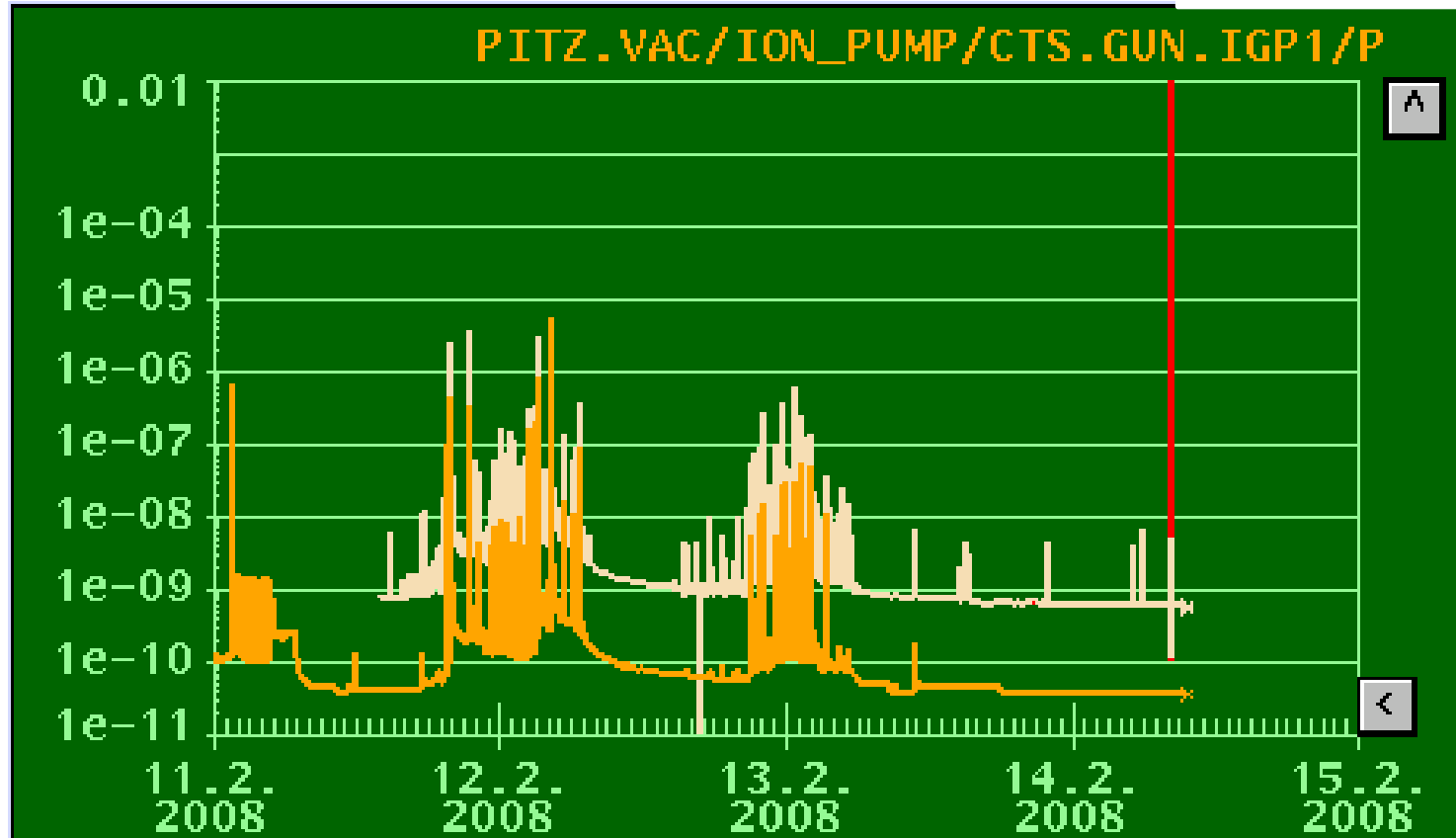


Gun.igp2  
(wave guide)

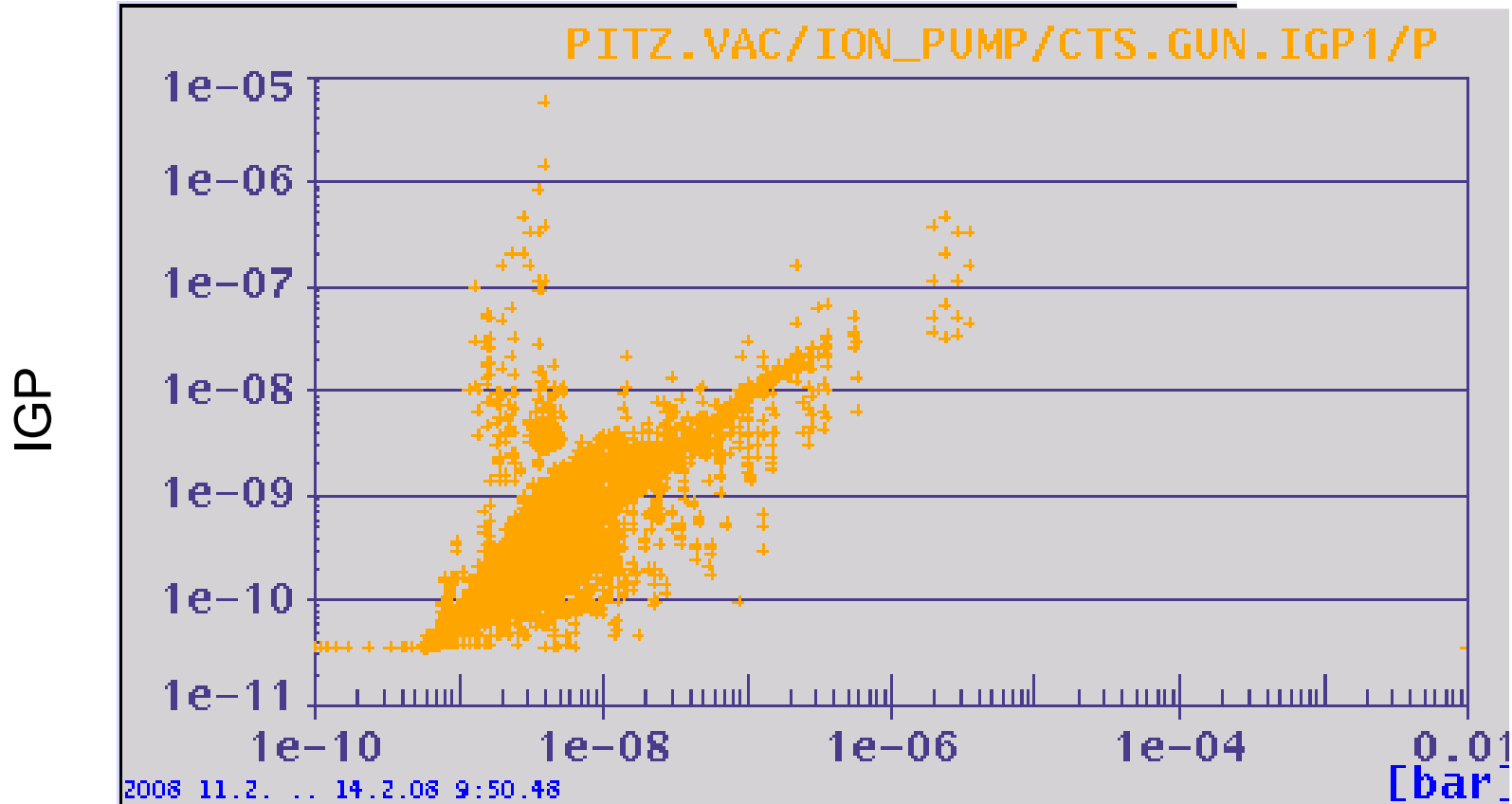
Gun.igp1  
(behind TSP)



X-Plot\_hist: PIZ.VAC/TPG300/CTS.GUN.PG1/P



X-Plot\_hist: PIZ.VAC/TPG300/CTS.GUN.PG1/P



Pressure gauge

# TITANIUM SUBLIMATION PUMPING (TSP)

Titanium Sublimation Pumps (TSPs) are often used in combination with ion pumps or independently to remove reactive gases from the vacuum environment. Combined with an ion pump, the TSP allows for low ultimate pressures in a shorter amount of time. All TSP components are bakeable to 400 °C.

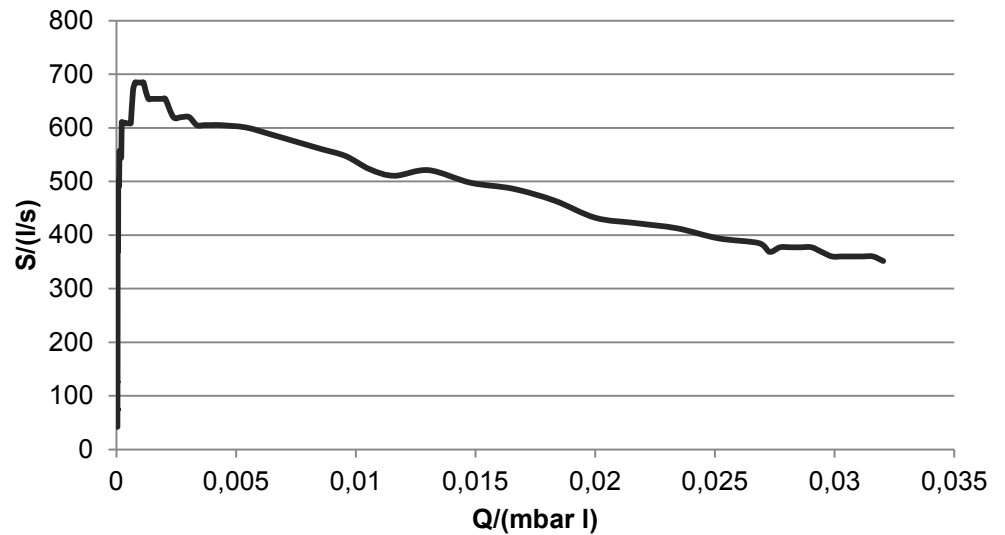
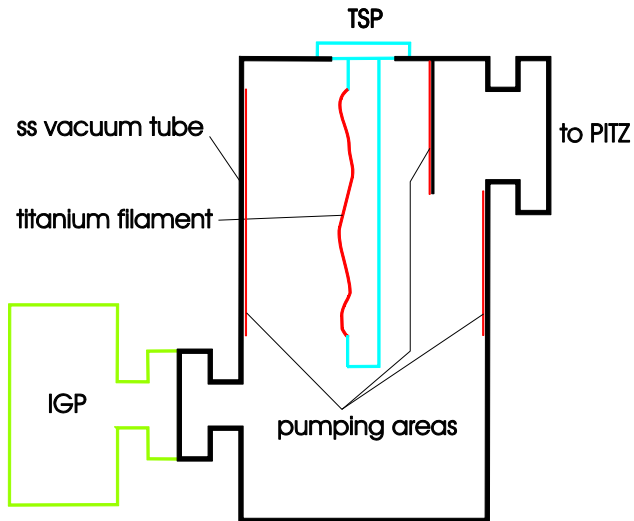
## TSP FILAMENT CARTRIDGE

The filament cartridge is mounted on a 2- 3/4" CFF (NW 35). The feedthrough supports three titanium-molybdenum filaments and a return path for ground isolation. Each filament contains 1.5 grams of usable titanium and averages 20 hours of operation.



# TSP arrangement at PITZ

pump procedure is the same  
as at the anode of an IGP

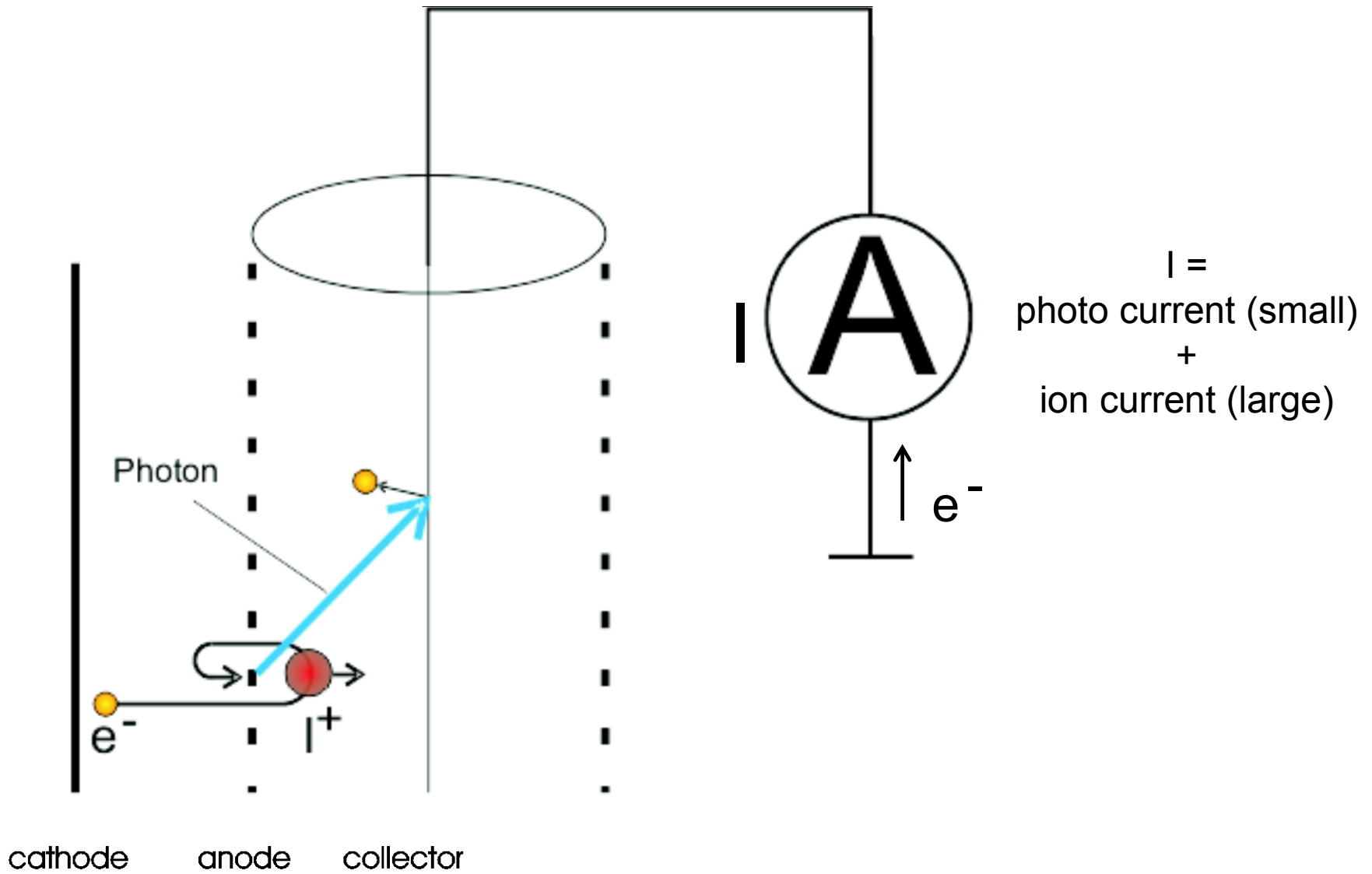


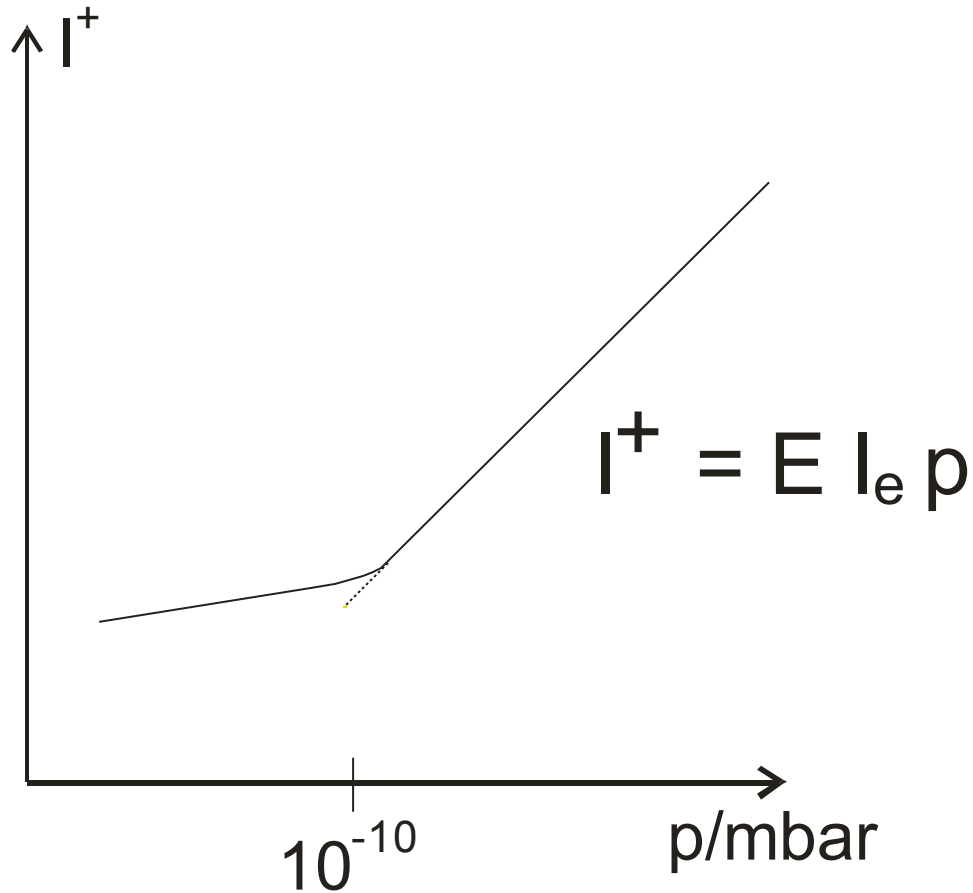
Pumping speed for noble gas = 0

Pumping speed decreases,  
if the pressure, i. e. the gas  
load, increases

# The Bayard Alpert pressure gauge

Hot cathode vacuum gauge for pressure in the range of some  $10^{-5}$  mbar down to  $1 \times 10^{-10}$  mbar

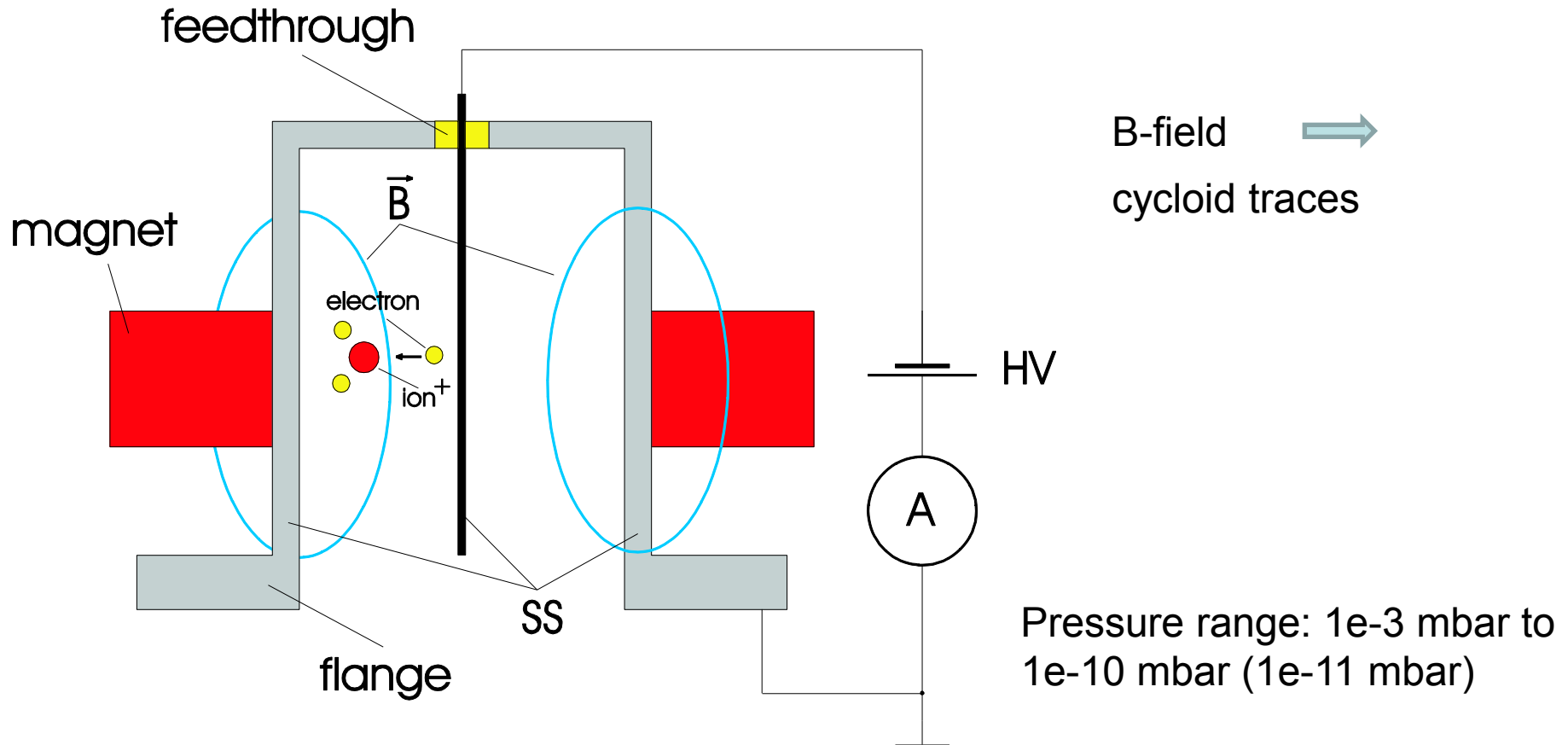




In the best case –  
 line function  $I^+ = I^+(p)$  down  
 to  $1 \cdot 10^{-10}$  mbar

After that –  
 photo current is not negligible

# Cold cathode vacuum gauge (Penning gauge)



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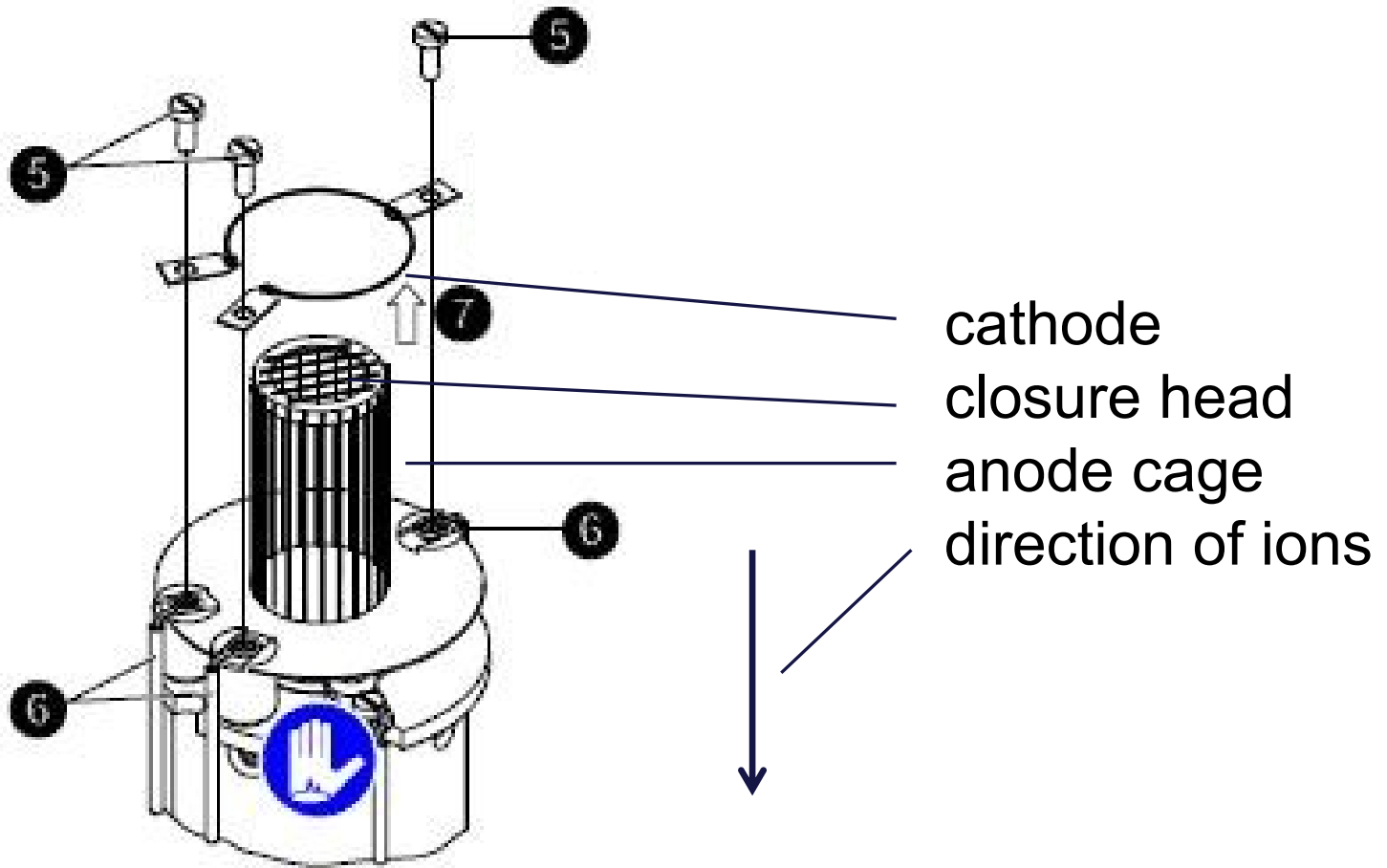


# Residual gas analyser

## Quadrupole mass spectrometer

- Measurement of partial pressure in the ultra high vacuum range
- All vacuum components mounted at PITZ are free of leaks and without pollution of hydrocarbons and other unrequested gases
- Therefore, the most interesting gases of the accelerator are only:
  - ❖ nitrogen, oxygen, argon (i. e. air), to detect a leak to the air
  - ❖ water, to detect a leak to the water cooling system
  - ❖ cracked components of  $SF_6$ , to detect a leak to the rf system

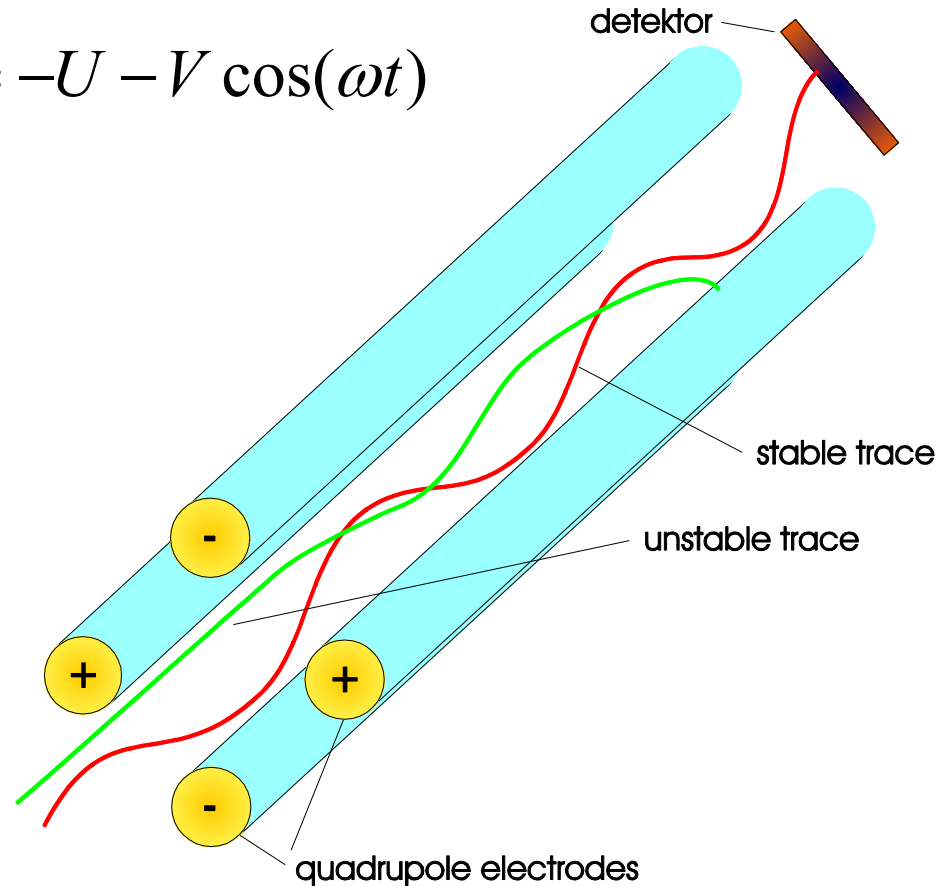
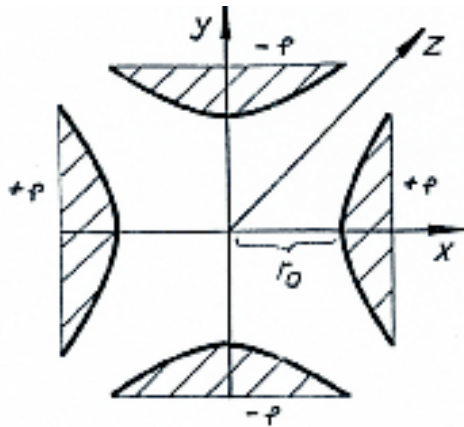
# Ion source of RGA



# Seperate ion system

$$+ \varphi = +U + V \cos(\omega t)$$

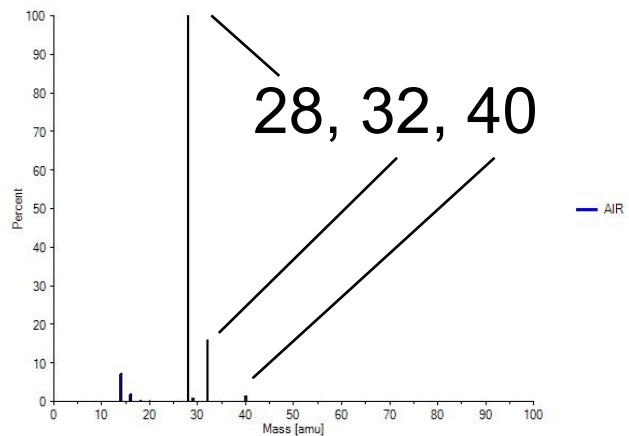
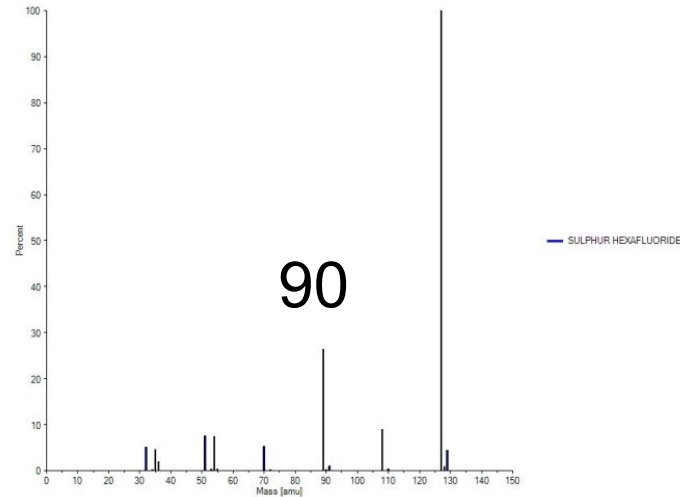
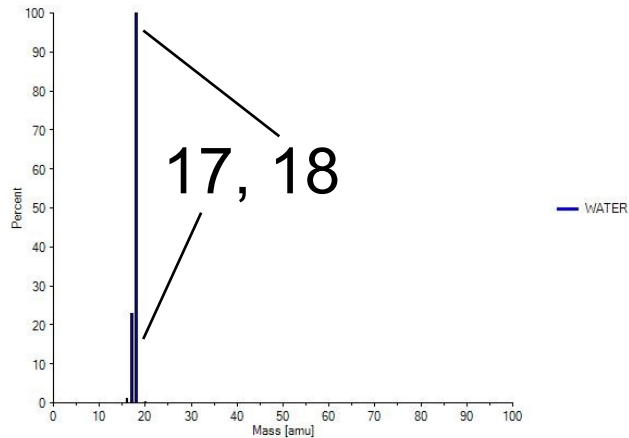
$$- \varphi = -U - V \cos(\omega t)$$



# Detector

- Faraday cup, high vacuum range, lower boundary line for concentration measurements: 100 ppm
- Channel electron multiplier, ultra high vacuum range, lower boundary line for concentration measurements: 10 ppm

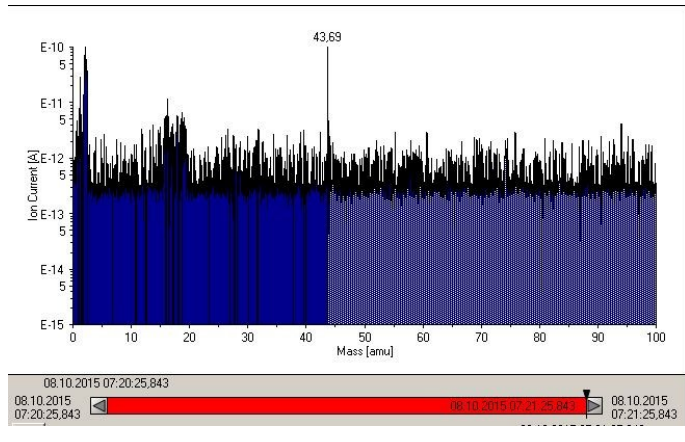
# Most interesting residual gas components



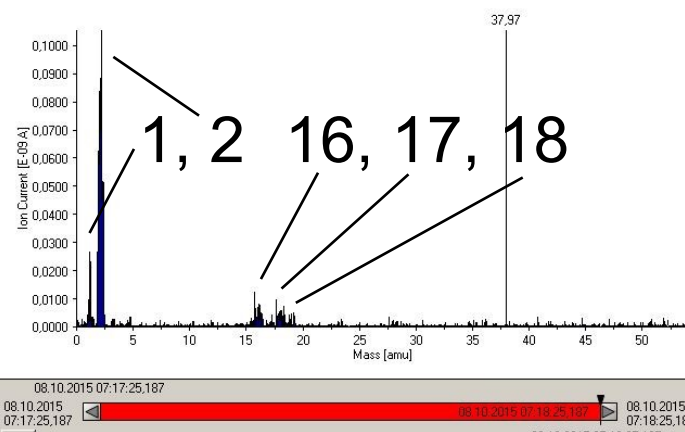
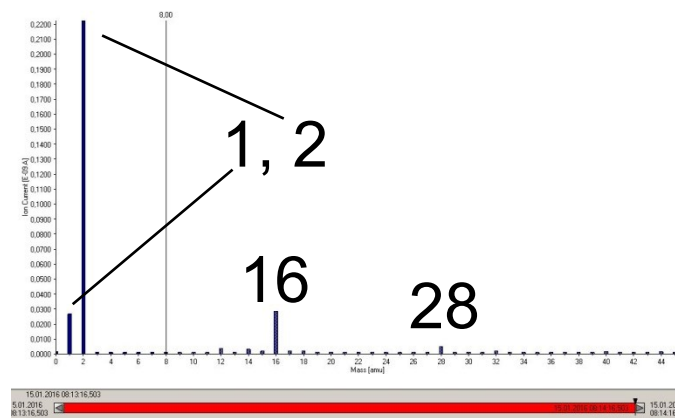
- gas particle can be cracked  $SF_6$ ,  $H_2O$
- gas particle can be ionized twice  
 $Ar^+ \leftrightarrow amu = 40$ ,  $Ar^{++} \leftrightarrow amu = 20$
- different gas particles can have the same atomic mass  $N_2, CO, CH_2^+ \leftrightarrow amu = 28$

# Some realistic examples

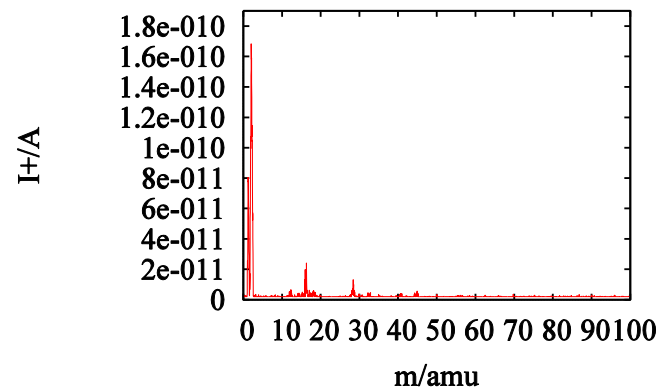
Gun 4.2 before taking apart



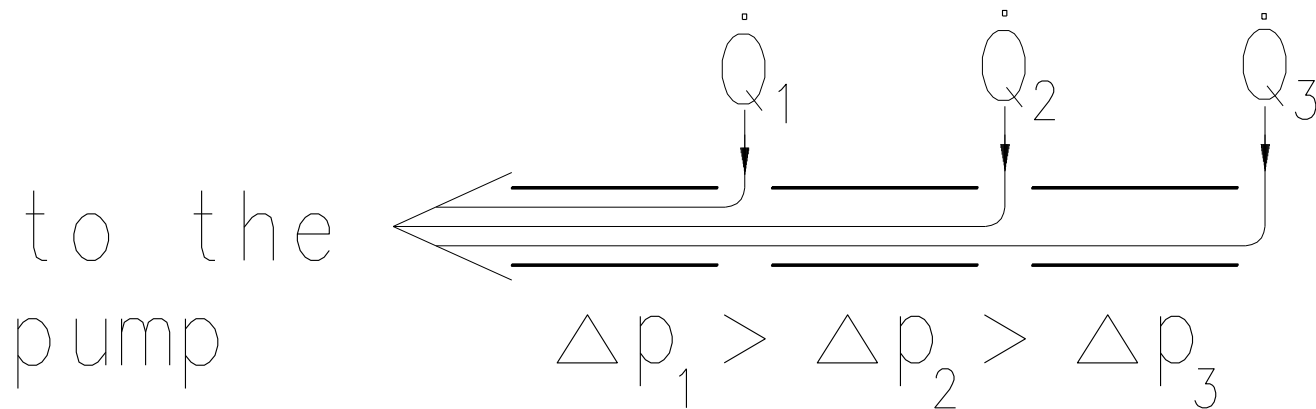
Booster  
1/15/2016

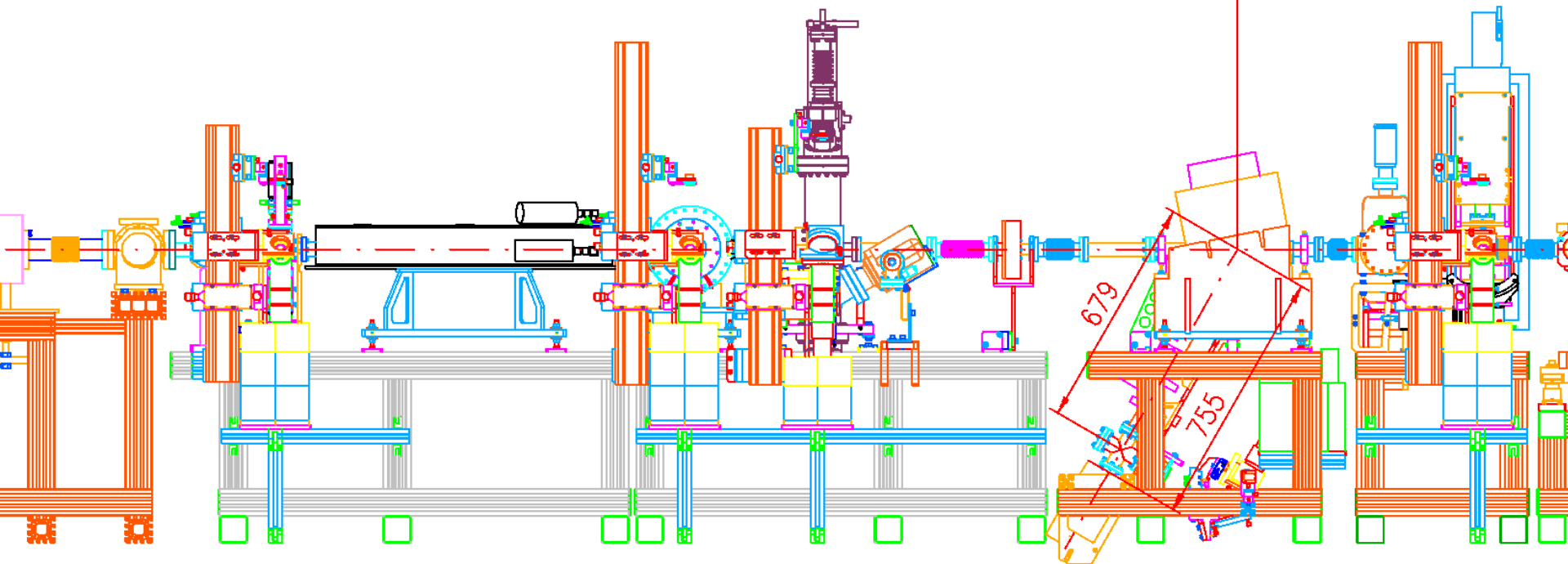


Booster



# Gas currents in an accelerator setup pressure gradients





Tolerierungsgrundsatz: ISO 8015  
 Oberflächenkenngrößen nach  
 DIN EN ISO 1302, 4287 bzw. 4288

Allg\_Toleranzen  
 nach DIN ISO 2768  
 Toleranzkl.:

Halbzeug:

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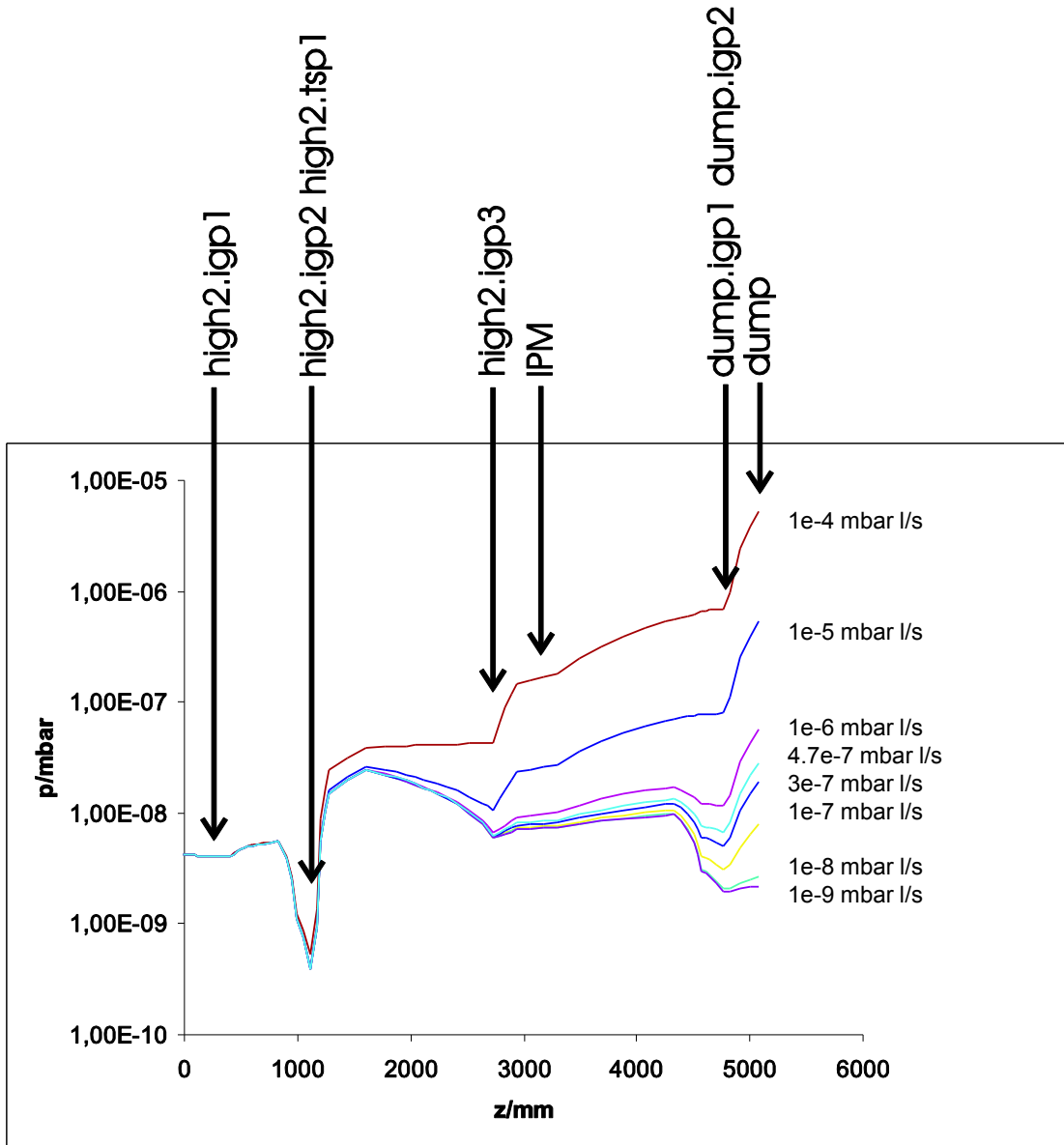
Schutzvermerk  
 DIN ISO 16016  
 (05-2002)  
 beachten

Maßstab:

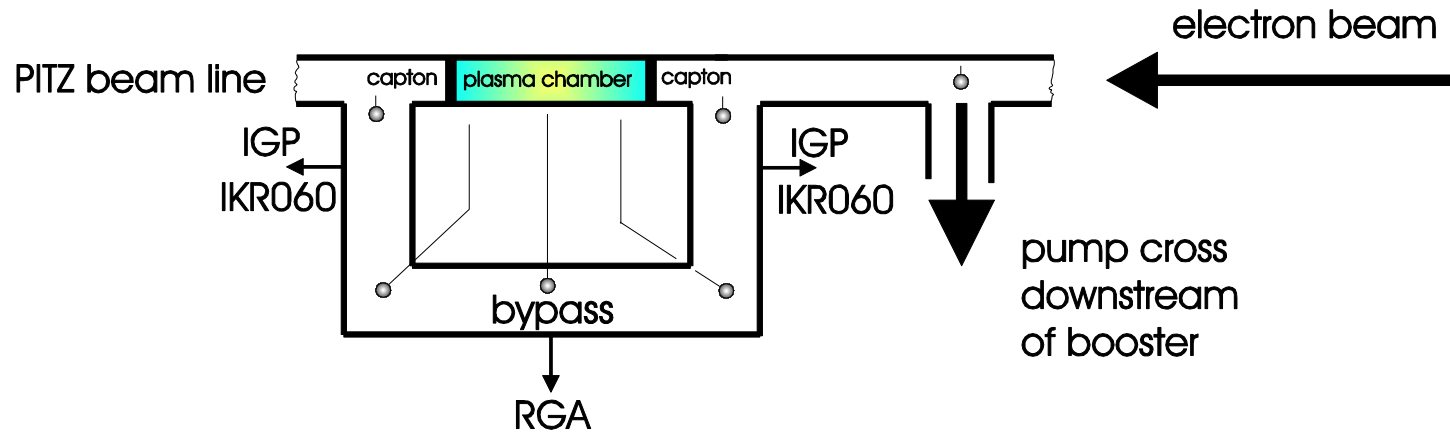
Werkstoff:



Pressure distributions  
depending on the gas  
load coming from  
the beam dump  
real value:  $4.7 \times 10^{-7}$  mbar l/s

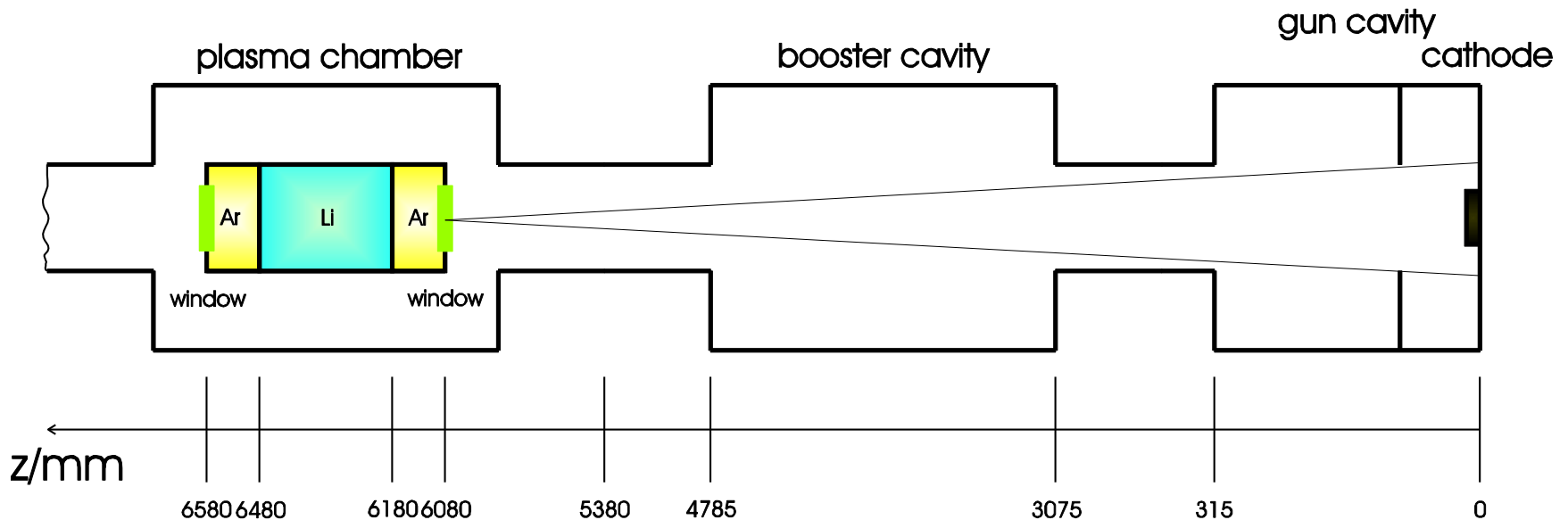


# Setup of the plasma chamber vacuum components



2 independent vacuum sensors to register an unrequested total pressure increase (IKR060)  
1 sensor to register an argon partial pressure increase and a vacuum leak potentially (RGA)

# Influence of the plasma chamber on the PITZ vacuum system

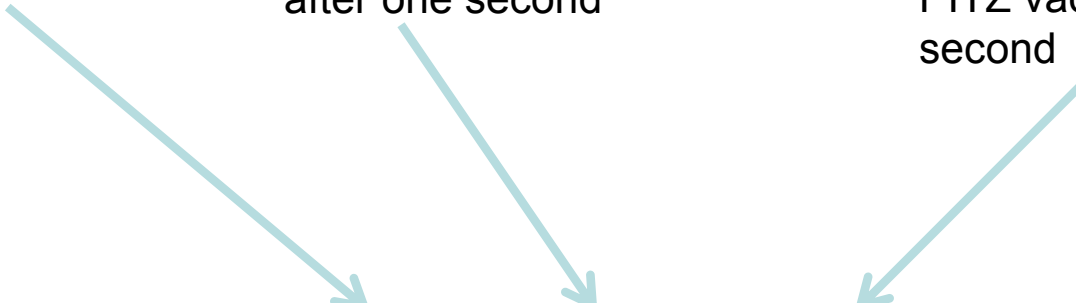


- permeation current passing the foil
- noble gas from the buffer passes a hole in the foil, possibly

diameter of hole

Pressure in the gas buffer  
after one second

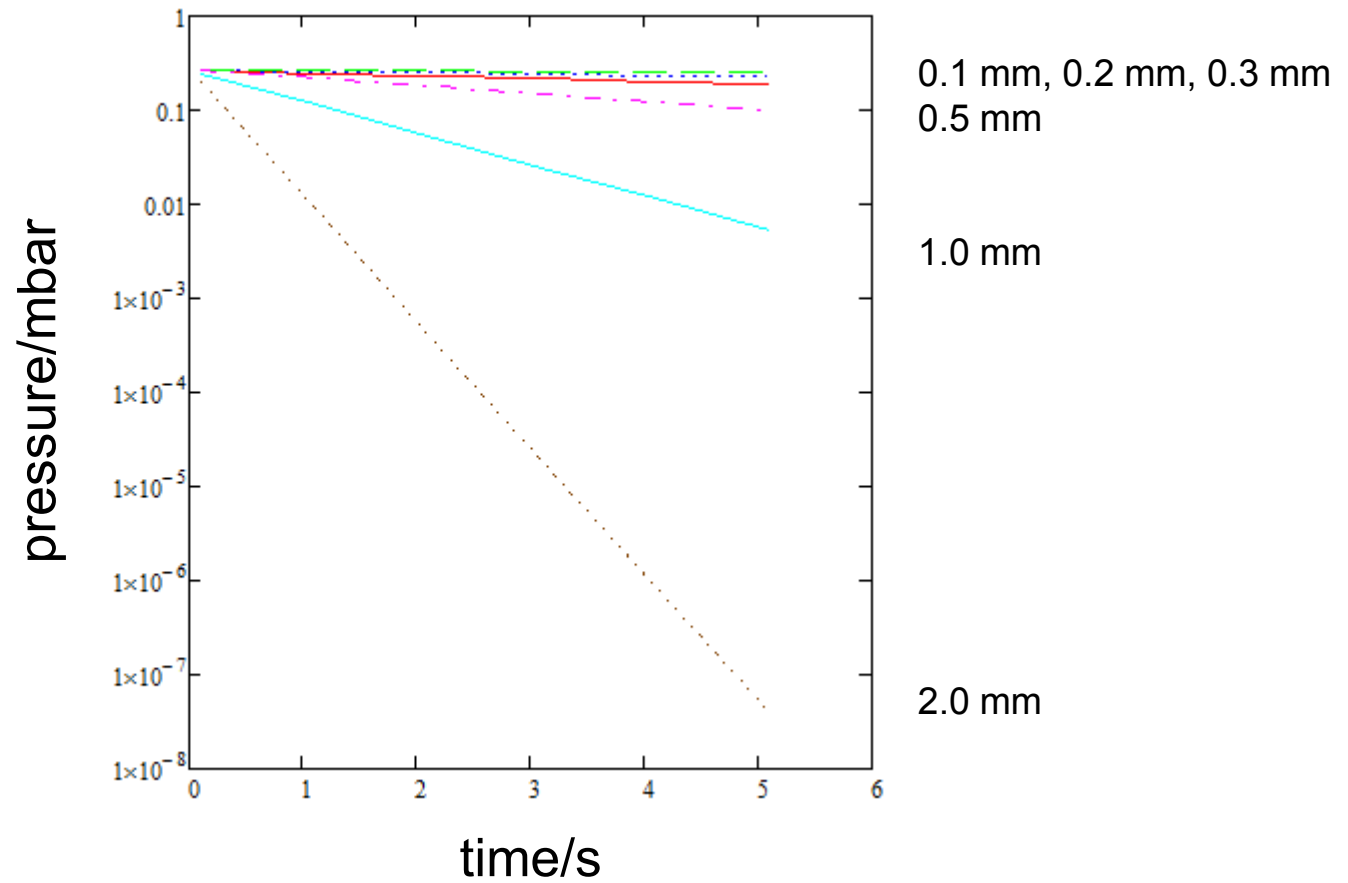
Li atoms passing the gas  
buffer and coming into the  
PITZ vacuum after one  
second



d/mm	p(t=1 s)/mbar	n
0,1	0,264	0
0,2	0,258	0
0,3	0,248	0
0,5	0,219	0
1	0,123	1,0E-14
2	0,0122	1,0E+13

# Ar pressure inside of the buffer volume vs. the time

Parameter: diameter of the hole



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# Gas kinetics

D. Richter. *Mechanik der Gase*. Springer-Verlag, Heidelberg Dordrecht London New York, 2010.

## Pressure distribution in vacuum chambers

D. Richter. Simulation of the BESSY II Vacuum System,  
Nuclear Instruments and Methods in Physics Research A , 470, p. 18-22, 2001

## Pressure measurement with ion getter pumps

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